

	Hits	Search Text	DBs
19	10	((etch\$4 or RIE or trim\$4) same (((top or upper) near9 (portion or surface or area or side)) or top) same (resist or photoresist) same pattern) and ((RIE or etch\$4 or trim\$4) near16 (sidewall or side or lateral or trim\$4) same (resist or photoresist) same pattern) and ("SO.sub.2" or (sulfur near6 \$3oxide)) and (((first near9 gas\$4) near26 (He or Ne or Ar or Kr or CO or (carbon near9 \$4oxide) or nitrogen or N\$2))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
20	20	((etch\$4 or RIE or trim\$4) same (((top or upper) near9 (portion or surface or area or side)) or top) same (resist or photoresist) same pattern) and ((RIE or etch\$4 or trim\$4) near16 (sidewall or side or lateral or trim\$4) same (resist or photoresist) same pattern) and (("SO.sub.2" or (sul\$2ur near2 \$3oxide)) near28 (etch\$4 or ash\$4 or remov\$4 or mill\$4)) and (((first near9 gas\$4) or etch\$4 or ash\$4 or mill\$4) near26 (He or Ne or Ar or Kr or CO or (carbon near9 \$4oxide) or nitrogen or N\$2))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
21	69	((resist or photoresist or photosensitive or (radiation near5 sensitive)) same pattern\$4 same (etch\$4 or (dry near5 etch\$4) or RIE or ash\$4 or mill\$4) same (sidewall or side\$8 or top\$3portion or top\$4area)) and develop\$4 and ((mill\$4 or ash\$4 or etch\$4 or RIE) same (gas\$4 or (inert\$4 near5 gas\$3) or plasma or ion\$3beam or ion\$4) same ((sulfur near2 oxide) or (sul\$3ur near2 \$2oxide) or ("SO.sub.2")) same (He or Ne or Ar or Xe or Kr or "N.sub.2") same (oxygen or "O.sub.2"))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
22	15	((resist or photoresist or photosensitive or (radiation near5 sensitive)) same pattern\$4 same (etch\$4 or (dry near5 etch\$4) or RIE or ash\$4 or mill\$4) same (sidewall or side\$8 or top\$3portion or top\$4area or taper\$4 or vertical\$4 or slop\$3)) and develop\$4 and ((mill\$4 or ash\$4 or etch\$4 or RIE) same (gas\$4 or (inert\$4 near5 gas\$3) or plasma or ion\$3beam or ion\$4) same ((sulfur near2 oxide) or (sul\$3ur near2 \$2oxide) or ("SO.sub.2") or (sul\$2ur near9 containing)) same (He or Ne or Ar or Xe or Kr or "N.sub.2" or helium or neon or argon or "CO" or "CO.sub.2") same (oxygen or "O.sub.2") same (sccm or (flow near9 rate)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB